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(54) **ACTINIC RAY-SENSITIVE OR RADIATION-SENSITIVE RESIN COMPOSITION, RESIST FILM, PATTERN FORMING METHOD, AND METHOD FOR PRODUCING ELECTRONIC DEVICE**

(57) Provided is an actinic ray-sensitive or radiation-sensitive resin composition capable of forming a pattern having excellent pattern line width roughness (LWR) and critical dimension uniformity (CDU). In addition, provided are a resist film, a pattern forming method, and a method for manufacturing an electronic device, for which the actinic ray-sensitive or radiation-sensitive resin composition is used. The actinic ray-sensitive or radiation-sensitive resin composition contains a resin having

an acid-decomposable group whose polarity increases through decomposition by the action of an acid, an acid generator A capable of generating a first acid upon irradiation with actinic rays or radiation, and an acid generator B capable of generating a second acid upon irradiation with actinic rays or radiation, and the first acid and the second acid satisfy predetermined requirements.

FIG. 2

